

UNITED STATES PATENT AND TRADEMARK OFFICE  
**CERTIFICATE OF CORRECTION**

PATENT NO. : 7,098,046 B2  
APPLICATION NO. : 10/801722  
DATED : August 29, 2006  
INVENTOR(S) : Yoshiharu Kataoka

Page 1 of 1

It is certified that error appears in the above-identified patent and that said Letters Patent is hereby corrected as shown below:

ON THE COVER PAGE:

In item "(57) **ABSTRACT**," please cancel the current abstract and insert the following therefor:

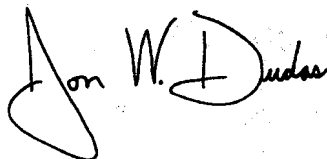
-- An exposure method of exposing a substrate to a pattern in which a mark in each of a plurality of layers on the substrate is detected for alignment of the substrate. The method includes illuminating a mark in each of a plurality of layers on a substrate, detecting an image of the illuminated mark in each of the plurality of layers, and setting an illumination condition in the illuminating step for the mark in each of the plurality of layers. --

COLUMN 6:

Line 41, "as," should read --  $\sigma$ s, --.

Signed and Sealed this

Twenty-first Day of August, 2007

A handwritten signature in black ink, reading "Jon W. Dudas". The signature is stylized, with a large loop for the "J" and a cursive "Dudas".

JON W. DUDAS  
*Director of the United States Patent and Trademark Office*